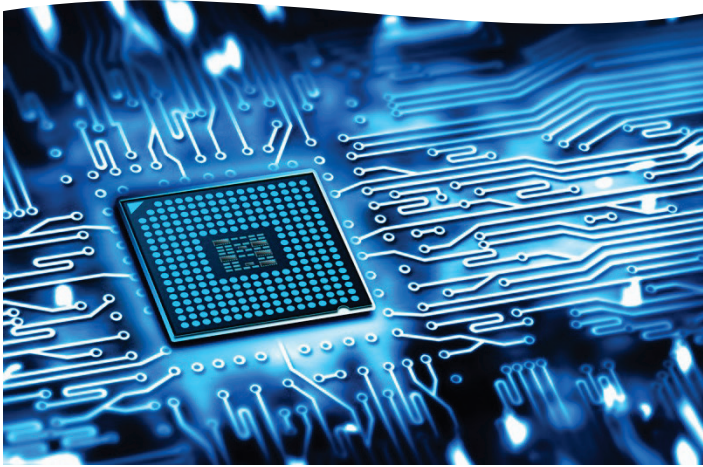


⁷²Ge in the Form of Germanium Tetrafluoride Gas for Semiconductor Manufacture



Enriched Germanium-74 in the form of Germanium Tetrafluoride gas is used as preamorphic implant to prevent silicon wafer from implant dopant channeling. Furthermore it is used to strain silicon wafer which optimizes the performance and speed of the device.

⁷²Ge in the Form of GeF₄ Gas

Specification

Physical properties:

- Material ⁷²Ge – Germanium-72 in the form of Germanium Tetrafluoride
- Enrichment ⁷²Ge \triangleq 50 – 53at%
⁷²Ge \triangleq 55 – 58at%

Chemical Properties:

- Form GeF₄
- Purity \geq 99.9vol%

Impurities in vppm

Ar	< 25
CO ₂	< 25
HF	< 25
N ₂	< 25
O ₂	< 25
SiF ₄	< 500
SO ₂	< 25

NUKEM Isotopes GmbH

Industriestrasse 13, 63755 Alzenau, Germany, T: +49 (0)6023 911611, F: +49 (0)6023 911614
E: info@nukemisotopes.de, I: www.nukem-isotopes.com